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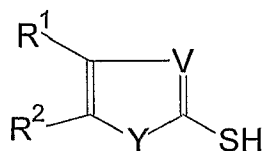
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(54) Title: NOVEL PHOTSENSITIVE RESIN COMPOSITIONS



(VI)

(57) Abstract: A photosensitive resin composition comprising: (a) at least one polybenzoxazole precursor polymer; (b) at least one compound having Structure VI wherein, V is CH or N, Y is O or NR<sup>3</sup> wherein R<sup>3</sup> is H, CH<sub>3</sub> or C<sub>2</sub>H<sub>5</sub>, R<sup>1</sup> and R<sup>2</sup> each independently are H, C<sub>1</sub> - C<sub>4</sub>

alkyl group, C<sub>1</sub> - C<sub>4</sub> alkoxy group, cyclopentyl or cyclohexyl, or alternatively, R<sup>1</sup> and R<sup>2</sup> can be fused to produce a substituted or unsubstituted benzene ring; and (c) at least one solvent; wherein the amount of the compound of Structure VI present in the composition is effective to inhibit residue from forming when the composition is coated on a substrate and the coated substrate is subsequently processed to form an image on the substrate, and with the proviso that if the polybenzoxazole precursor polymer solely consists of polybenzoxazole precursor polymers that do not contain a photoactive moiety in the polymer, then (d) at least one photoactive compound is also present in the composition.. The present invention also concerns a process for forming a relief pattern and electronic parts using the composition.



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## INTERNATIONAL SEARCH REPORT

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## A. CLASSIFICATION OF SUBJECT MATTER

## INT. CL.

G03C 1/73 (2006.01) G03F 7/027 (2006.01) C08K 5/37 (2006.01)

G03F 7/004 (2006.01) G03F 7/039 (2006.01)

## U.S. CL.

430/270.1 ; 430/18

According to International Patent Classification (IPC) or to both national classification and IPC

## B. FIELDS SEARCHED

Minimum documentation searched (classification system followed by classification symbols)

Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched

Electronic data base consulted during the international search (name of data base and, where practicable, search terms used)

CA; WPIDS: structure search (formula VI)+ ?thiol?, photo?, photosens?, photoresist?

## C. DOCUMENTS CONSIDERED TO BE RELEVANT

Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
A	US 3645772 A (JONES) 29 February 1972 (see whole document)	1-26
A	US 3873316 A (VELTEN et. al.) 25 March 1975 (see whole document)	1-26
X	US 6001517 A (KAWAMONZEN) 14 December 1999 (see whole document)	1

 Further documents are listed in the continuation of Box C See patent family annex

* Special categories of cited documents:		
"A" document defining the general state of the art which is not considered to be of particular relevance	"T" later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention	
"E" earlier application or patent but published on or after the international filing date	"X" document of particular relevance; the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone	
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"O" document referring to an oral disclosure, use, exhibition or other means	"&" document member of the same patent family	
"P" document published prior to the international filing date but later than the priority date claimed		

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C (Continuation). DOCUMENTS CONSIDERED TO BE RELEVANT		
Category*	Citation of document, with indication, where appropriate, of the relevant passages	Relevant to claim No.
X	US 6183934 B1 (KAWAMONZEN) 6 February 2001 (see whole document)	1
X	US 6159654 A (MACHIDA et. al.) 12 December 2000 (see whole document)	1
X	JP 2004264537 A (HITACHI CHEMICAL DUPONT MICROSYSTEMS LTD) 24 September 2004 (see English translation of full document obtained from JAPIO website: URL: <a href="http://www4.ipdl.inpit.go.jp/Tokujitu/PAJdetail.ipdl?N0000=60&amp;N0120=01&amp;N2001=2&amp;N3001=2004-264537">http://www4.ipdl.inpit.go.jp/Tokujitu/PAJdetail.ipdl?N0000=60&amp;N0120=01&amp;N2001=2&amp;N3001=2004-264537</a> )	1
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P, X	Derwent Abstract No. 2005-785981/80 & WO 2005/101125 A1 (HITACHI CHEMICAL DUPONT MICROSYSTEMS LTD) 27 October 2005 (see Derwent Abstract)	1
A	GI XUE et. al. "The formation of an effective anti-corrosion film on copper surfaces from 2-mercaptobenzimidazole solution" J. Electroanal. Chem., vol. 310, 1991, p.p. 139-148 (see whole document)	1-26
A	JIAN DONG et al. "Studies of polyimide/copper interface and its improvement by a two-component primer" Die Angewandte Makromolekulare Chemie vol. 230 (4044) 1995, p.p. 143 -157 (see whole document)	1-26

## INTERNATIONAL SEARCH REPORT

Information on patent family members

International application No.

PCT/US2006/10394

This Annex lists the known "A" publication level patent family members relating to the patent documents cited in the above-mentioned international search report. These particulars are merely given for the purpose of information.

Patent Document Cited in Search Report	Patent Family Member					
US 3645772						
US 3873316	BE 768258	CA 962503	CH 570639			
	DE 2028773	ES 392064	FR 2096217			
	GB 1337825	NL 7107486	SU 429599			
US 6001517	JP 10186659					
US 6159654	JP 9297400					
US 6183934	JP 11072918					
JP 9316326						
JP 2004264537						
WO 2005101125						
END OF ANNEX						